



Attorney's Docket No.: 10559-879001/P17481
Intel Corporation

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Yan Borodovsky
Serial No.: 10/688,306
Filed : October 17, 2003
Assignee : Intel Corporation
Title : COMPOSITE PRINTING

Art Unit: 2851
Examiner: R. Fuller

Mail Stop Amendment

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicants call attention to the attached Information
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Kindly accept this Information Disclosure Statement under
Rule 97(c)(2). The rule 17(p) certification fee of \$180 is
enclosed.

The documents are in the English language; hence no concise
explanation is necessary per Rule 98(a)(3).

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Page 2 of 2

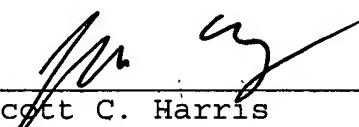
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Examiner's initials in the left column per MPEP 609 are
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Respectfully submitted,

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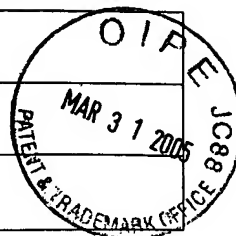
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Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-879001	Application No. 10/688,306
Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Yan Borodovsky	
		Filing Date October 17, 2003	Group Art Unit 2851



U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AE							
	AF							
	AG							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
	AH	M. Fritze, et al., "Gratings of regular arrays and trim exposures for ultralarge scale integrated circuit phase-shift lithography", <i>J. of Vacuum Science & Technology B</i> , 19(6):2366-2370, Nov/Dec 2001.
	AI	J.A. Hoffnagle, et al., "Liquid immersion deep-ultraviolet interferometric lithography", <i>J. of Vacuum Science & Technology B</i> , 17(6):3306-3309, Nov/Dec 1999.
	AJ	Marc D. Levenson, et al., "Exposing the DUV SCAAM - 75 nm Imaging on the Cheap!", <i>Proc. of SPIE: Design, Process Integration, and Characterization for Microelectronics</i> , 4692:288-297, March 2002.
	AK	Alex K. Raub, et al., "Deep UV immersion interferometric lithography", <i>Proc. of SPIE: Optical Microlithography XVI</i> , 5040:667-678, Feb. 2003.
	AL	Bruce W. Smith, et al., "Water immersion optical lithography at 193 nm", <i>J. Microlith., Microfab., Microsyst.</i> , 3(1):44-51, Jan. 2004.
	AM	Akiyoshi Susuki, et al., "Multilevel imaging system realizing $k_1 \approx 0.3$ lithography", <i>Proc. of SPIE: Optical Microlithography XII</i> , 3679:396-407, Mar. 1999.
	AN	M. Switkes, et al., "Extending optics to 50 nm and beyond with immersion lithography", <i>J. of Vacuum Science & Technology B</i> , 21(6):2794-2799, Nov/Dec 2003.
	AO	Brian Tyrrell, et al., "Investigation of the physical and practical limits of dense-only phase shift lithography for circuit feature definition", <i>J. Microlith., Microfab., Microsyst.</i> , 1(3):244-252, Oct. 2002.
	AP	Saleem H. Zaidi, et al., "Multiple exposure interferometric lithography", <i>Proc. of SPIE: Optical Microlithography VII</i> , 2197:869-875, Mar. 1994.
	AQ	M. Fritze, et al., "Preprint of poster presentation entitled "High-Throughput Hybrid Optical Maskless Lithography: All-Optical 32-nm Node Imaging," Presented at SPIE Microlithography 2005, San Jose, California, USA, March 3, 2005.

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	